

PRELIMINARY AMENDMENT  
Continuation of U.S. Appln. No. 09/023,801

An action from the office is respectfully requested.

Respectfully submitted,



Brett S. Sylvester  
Registration No. 32,765

SUGHRUE, MION, ZINN,  
MACPEAK & SEAS, PLLC  
2100 Pennsylvania Avenue, N.W.  
Washington, D.C. 20037-3213  
Telephone: (202) 293-7060  
Facsimile: (202) 293-7860

Date: December 6, 2000

## APPENDIX

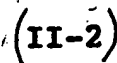
### Marked up version of claims

6. (Amended) A positive [type] photoresist composition comprising a resin which



wherein R<sub>21</sub> to R<sub>24</sub>, which may be the same or different, each represents a hydrogen atom or an alkyl group; and m represents 1 or 2.

7. (Amended) The positive [type] photoresist composition according to claim 6,



wherein  $R_{21}$  to  $R_{24}$  and  $m$  have the same meanings as given in claim 6;  $R_{25}$  represents a hydrogen atom or a methyl group; and  $A_{21}$  represents one group selected from the group consisting of a single bond, an alkylene group, a substituted alkylene group, an ether group, a thioether group, a carbonyl group, an ester group, an amido group, a sulfonamido group, a urethane group and a urea group, or a combination of two or more of them.

8. (Amended) The positive [type] photoresist composition according to claim 6 or 7, wherein said resin further contains repeating structure units each having an alicyclic hydrocarbon moiety.

9. (Amended) The positive [type] photoresist composition according to [any one of claims] claim 6 [to 8] or 7, wherein said resin further contains repeating structure units each having a group which is decomposed by action of an acid to increase solubility in an alkali developing solution.